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友情链接

- ▶ 厦门大学
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刘东平

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个人简历:

刘东平, 1971年11月出生, 教授, 博士生导师。2001年3月在大连理工大学获博士学位, 2001年4月-2006年6月先后在德国代根多夫应用科技大学和美国科罗拉多州立大学做博士后研究工作。研究工作主要集中在多种等离子体应用研究及等离子体诊断分析工作。在多种低温等离子体设计与应用, 如射频等离子体、介质阻挡等离子体、微波等离子体、辉光放电等离子体、阴极真空弧放电、磁控溅射等离子体等具有多年的工作基础。以第一或通讯作者在Appl. Phys. Lett., J. Appl. Phys., ACS-Appl. Mater. Interface, Chem. Phys. Lett.等SCI杂志上发表论文约50篇, 主编译著1部。曾荣获德国代根多夫城市高校科研奖(奖金5000欧元)。

研究方向:

低温等离子体物理(等离子体化学)

科研项目

- ▶ 暂无

代表性论文

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- ▶ 3. Dongping Liu, G. Benstetter, E. Lodermeier, J.L. Zhang, Y.H. Liu and J. Vancea: "Filtered pulsed carbon cathodic arc: plasma and amorphous carbon properties" J. Appl. Phys. 2004, 95: 7624-7631.
- ▶ 4. Dongping Liu, J.L. Zhang, Y.H. Liu, J. Xu, and G. Benstetter: "Growth processes and surface properties of diamond-like films" J. Appl. Phys. 2005, 97: 104901.
- ▶ 5. Dongping Liu, G. Benstetter, and W. Frammelsberger: "Nanoscale electron field emission from the bare, hydrogenated and graphite-like layer covered tetrahedral amorphous carbon films" J. Appl. Phys. 2006, 99: 44303-44310.
- ▶ 6. Dongping Liu, Jie Zhou, Ellen R Fisher, "Correlation of Gas-Phase Composition with Film Properties in the Plasma-Enhanced Chemical Vapor Deposition of Hydrogenated Amorphous Carbon Nitride Films" J. Appl. Phys. 2007, 101: 023304-023312.
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- ▶ 10. Dacheng Wang, Di Zhao, Kecheng Feng, Xianhui Zhang, Dongping Liu*, and Size Yang, "The cold and atmospheric-pressure air surface

barrier discharge plasma for large-area sterilization applications” Appl. Phys. Lett. 2011, 98: 161501-161503.

著作

▶ 暂无

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